

ABSTRACT OF THE DISCLOSURE

RESIST COMPOSITION CONTAINING SPECIFIC CROSS-LINKING AGENT

A resist composition comprising an alkali-soluble polymer, a special cross-linking agent containing one or more oxirane rings and at least one of -O-, -CO-, -COO- and -OCO- groups in the molecule, a photoacid generator, and a solvent can form a film having high transmittance for deep UV light such as ArF excimer laser beams and high etching resistance as well as high resolution, and thus suitable for forming a negative working pattern.